	Hits	Search Text	DBs
8	329	((system or apparatus or module or first) same (diffract$4 or (interference same pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (width or line$2width) same (feature or line or pitch) same (apparatus or system or module) same (imprint or e$2beam or optical or ion$3beam or X$3ray))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	19	((system or apparatus or module or first) same (diffract$4 or (interference same pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3) same line$2width same (feature or line or pitch) same (apparatus or system or module) same (imprint or e$2beam or optical or ion$3beam or X$3ray))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	103	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near12 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	102	S11 NOT S10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	50	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near6 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray) same (mask$3 or reticle or photomask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	44	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near6 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and (mask or reticle or photomask) and ((dual or double or plural$3) same (expos$4 or irradiat$4 or illuminat$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	33	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near6 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and (mask or reticle or photomask) and ((dual or double or plural$3) near16 (expos$4 or irradiat$4 or illuminat$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	58	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near6 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and (mask or reticle or photomask) and ((dual or double or plural$3 or second) near16 (expos$4 or irradiat$4 or illuminat$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	1	((system or apparatus or module) same ((diffract$4 or interference) near16 (grating or pattern))) and ((expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3 or double or dual)) and (imprint$3 near9 (system or apparatus or method or lithograph$5)) and (e$2beam near12 (source or system or method or apparatus or expos$3)) and (ion$3beam near9 (lithograph$5 or source or expos$4 or system or apparatus or chamber)) and (X$3ray near12 (lithograph$4 or expos$4 or system or apparatus or source))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	4	((system or apparatus or module) same ((diffract$4 or interference) near16 (grating or pattern))) and ((expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3 or double or dual)) and (e$2beam near12 (source or system or method or apparatus or expos$3)) and (ion$3beam near9 (lithograph$5 or source or expos$4 or system or apparatus or chamber)) and (X$3ray near12 (lithograph$4 or expos$4 or system or apparatus or source))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	1	430/394.ccls. and (diffract$4 or interference) and (e$2beam near12 (source or system or method or apparatus or expos$3 or irradiat$4)) and (ion$3beam near9 (lithograph$5 or source or expos$4 or system or apparatus or chamber or irradiat$4 or illuminat$4)) and (X$3ray near12 ($6lithograph$4 or expos$4 or system or apparatus or source))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	13	((system or apparatus or module) same ((diffract$4 or interference) near16 (grating or pattern))) and ((expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3 or double or dual)) and ((e$2beam or (electron near2 beam)) near12 (source or system or method or apparatus or expos$3)) and (ion$3beam near9 (lithograph$5 or source or expos$4 or system or apparatus or chamber)) and (X$3ray near12 (lithograph$4 or expos$4 or system or apparatus or source))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	6	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near6 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and ((mask or reticle or photomask) same (OPC or (optical near6 proximit$4 near6 correct$4))) and ((dual or double or plural$3 or second) near16 (expos$4 or irradiat$4 or illuminat$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	6	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same ((diffract$4 or interference) near6 (grating or pattern))) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and ((mask or reticle or photomask) same (OPC or (optical near6 proximit$4 near6 correct$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
22	18	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4) same (first or initial)) and ((second or double or multiple) same (expos$4 or illuminat$4 or irradiat$4) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and ((mask or reticle or photomask) same (OPC or (optical near6 proximit$4 near6 correct$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	13	S23 NOT S22	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	1	((beam near9 split$4) same ((diffract$4 or interference) near16 (grating or pattern))) and ((expos$4 or illuminat$4 or irradiat$4) same (second or multiple or plural$3 or double or dual)) and ((e$2beam or (electron near2 beam)) near12 (source or system or method or apparatus or expos$3)) and (ion$3beam near9 (lithograph$5 or source or expos$4 or system or apparatus or chamber)) and (X$3ray near12 (lithograph$4 or expos$4 or system or apparatus or source))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	12	((system or apparatus or module) same (expos$4 or irradiat$4 or illuminat$4)) and ((expos$4 or illuminat$4 or irradiat$4) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray) same (mask or reticle or photomask) same (OPC or serif$2 or (optical near6 proximit$4 near6 correct$4)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	5	((expos$4 or illuminat$4 or irradiat$4) same (apparatus or system or module) same (imprint or e$2beam or ion$3beam or X$3ray)) and ((mask or reticle or photomask) same (OPC or serif$2 or (optical near6 proximit$4 near6 correct$4)) same (feature or (aspect near9 ratio) or pattern) same (adjust$4 or chang$4 or vary$4 or variable) same width)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
27	2	((mask or reticle or photomask) same (print$4 or imprint$4 or pattern$4) same (Boolean near16 subtract$4) same (design or layout) same (interference or diffract$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	4	((mask or reticle or photomask) same (Boolean near16 subtract$4) same (design or layout or pattern$4)) and (interference or diffract$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	8	(mask or reticle or photomask) and ((Boolean near16 subtract$4) same (design or layout or pattern$4)) and (interference or diffract$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB